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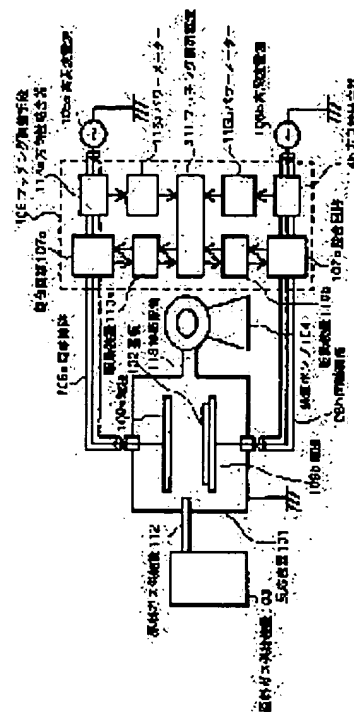
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(54) METHOD AND APPARATUS FOR VACUUM TREATMENT

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a method for vacuum treatment, which can improve operability for matching adjustment, and reproducibility of the matching condition, and shorten adjusting time for matching, when performing vacuum treatment while applying several high-frequency powers at the same time, and provide an apparatus for vacuum treatment.

SOLUTION: In the method for vacuum treatment, which mounts a substrate to be treated 102 in a reaction vessel 101 capable of being depressurized, introduces a source gas, generates plasma of the source gas by a high-frequency power, and treats the substrate to be treated, this method is characterized by supplying several high-frequency powers to an electrode 109a through matching circuits 107a and 107b, detecting at least either the state of the several matching circuits or the matching state of the high-frequency power, and adjusting the several matching circuits with a matching control circuit 111 through feeding back the detected results.



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